In the Specification:

Please amend the paragraph beginning on page 6, line 3 to appear as indicated in the following:

Simultaneous capacitive coupling (indicated by E in FIGs. 1 and 2) and inductive coupling (indicated by B in Figs. 1 and 2) creates zero points in the transmission function. That means that at particular frequencies, no signal is transferred. This phenomenon is known for comb filters, for instance, if the lines are exactly $\lambda/4$ long.

Please amend the paragraph beginning on page 8, line 1 to appear as indicated in the following:

A resonator according to a further embodiment of the invention is shown in FIG. 2. Here, the conducting track structures 20, 22 are designed spiral-shaped, the beginning 24 and the end 26 are linked to each other via a coupling member 28, so that they are at the same, floating potential. Coupling member 28 is indicated as forming a lead-through through the insulating layer disposed between the conducting track structures, and can also be formed as a non-overlapping extension of the conducting track structures.

Please amend the paragraph beginning on page 9, line 9 to appear as indicated in the following:

Since, dependent upon manufacturing, the metal layers of the conducting track structures are not perfectly aligned one over the other, variations in the distributed capacitance and inductance of the conducting tracks is to be expected. FIG. 9a shows an uncompensated structure in which two conducting tracks of width b are arranged with an offset v above and below a dielectric layer of thickness d. The effects of this unwanted offset v on the resonant frequency may be compensated for with additional conducting track of width $2k$ (total width $b + 2k$), as shown in FIG. 9b, where k is chosen to be at least 70%, and in one example approximately equal to, the maximum position offset v plus half the layer thickness d of the dielectric layer. The effects of the position offset on an arrangement with two b=450 μm-wide conducting tracks for a layer sequence shown in FIG. 4 with d=25 μm are shown in FIG. 10. The dashed curves are the results for the uncompensated

structure with k=0 μm according to FIG. 9a and the continuous curves are the results for a compensated structure with k=50 μm according to FIG. 9b.